



NOTES

1. COATING(S1): HIGH ENERGY LASER LINE COATING
Rs, Rp > 99% @ 532 nm, 45° AOI
2. CLEAR APERTURE(S1, S2): > 90% CA
3. SURFACE QUALITY(S1): 20/10(S/D)
(S2): 60/40(S/D)
4. SURFACE FLATNESS(S1): $\lambda/6 @ 633 \text{ nm}$
5. PARALLELISM(S1, S2): < 3 arcmin
6. CHAMFER: < 0.2 mm, 45°
7. THICKNESS TOLERANCE: $\pm 0.25 \text{ mm}$
8. DIAMETER TOLERANCE: $+0/-0.1 \text{ mm}$
9. OTHER SURFACES: FINE GROUND
10. DAMAGE THRESHOLD: $8 \text{ J/cm}^2 @ 532 \text{ nm}, 10 \text{ ns}, 20 \text{ Hz}$

DRAWING PROJECTION			LBTEK			
	NAME	DATE	LPM10-532P-HP			
DRAWN	LZHOU	Aug. /5th/24	HIGH ENERGY LASER LINE MIRROR Ø 25.4 mm x 6.0 mm, 532 nm			
APPROVAL	WCHENG	Aug. /5th/24	MATERIAL	WEIGHT	SCALE	REV
FOR INFORMATION ONLY NOT FOR MANUFACTURING PURPOSES			UVFS	6.7 g	2:1	A